

US006485602B2

(12) United States Patent Hirose

US 6,485,602 B2 (10) Patent No.:

(45) Date of Patent: Nov. 26, 2002

(54) PLASMA PROCESSING APPARATUS

Inventor: Eiji Hirose, Nirasaki (JP)

Assignee: Tokyo Electron Limited, Tokyo (JP)

(*) Notice: Subject to any disclaimer, the term of this

patent is extended or adjusted under 35

U.S.C. 154(b) by 0 days.

Appl. No.: 09/906,731 (21)

(22)Filed: Jul. 18, 2001

(65)**Prior Publication Data**

US 2002/0007915 A1 Jan. 24, 2002

(30)Foreign Application Priority Data

(JP) 2000-219783

(51) Int. Cl.⁷ H01L 21/00

U.S. Cl. 156/345.44; 156/345.47;

156/345.47; 118/723 E; 204/298.08, 298.34

(56)References Cited

U.S. PATENT DOCUMENTS

5,900,103 A * 5/1999 Tomoyasu et al. 118/723 E

FOREIGN PATENT DOCUMENTS

JP 2001-7086 1/2001

* cited by examiner

Primary Examiner—Thi Dang

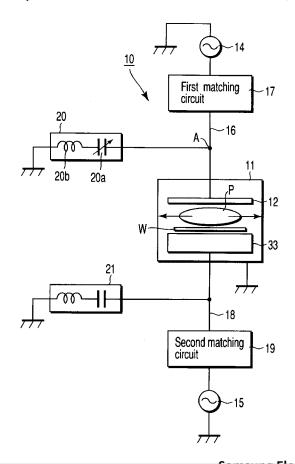
(74) Attorney, Agent, or Firm—Oblon, Spivak, McClelland,

Maier & Neustadt, P.C.

ABSTRACT (57)

The present invention concerns a plasma processing apparatus for processing a processing object by applying two types of high-frequency power with different frequencies to generate plasma. A first high-frequency line is provided with a first filter circuit for attenuating a high-frequency current from a second high-frequency power supply. A second high-frequency line is provided with a second filter circuit for attenuating a high-frequency current from a first highfrequency power supply. The first filter circuit is provided with a variable capacitor for changing a circuit constant. For changing the circuit constant, the variable capacitor is varied so that a resonance point becomes greater than an optimum resonance point most attenuating a high frequency in the second high-frequency power supply. Doing so decreases a sputter rate of the generated plasma affected on a wall surface of the processing chamber.

7 Claims, 7 Drawing Sheets





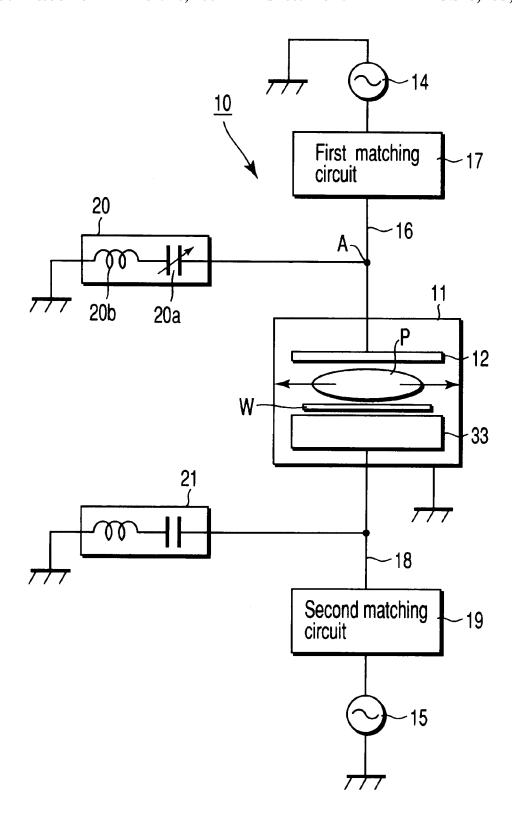
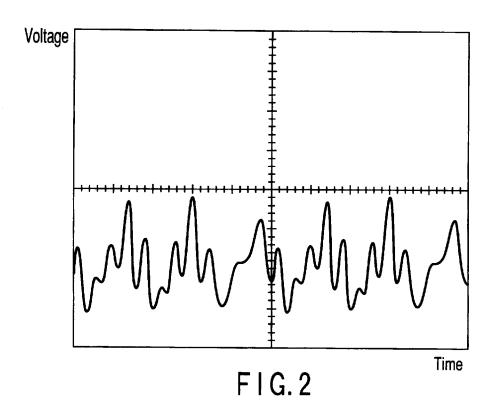
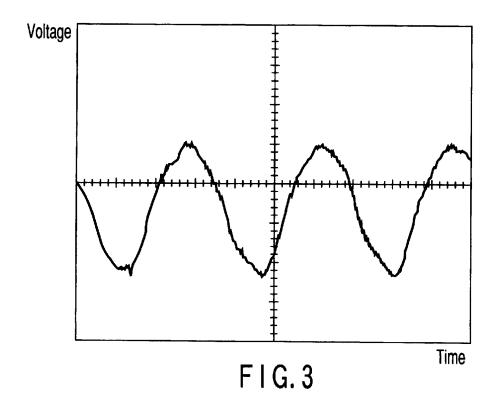


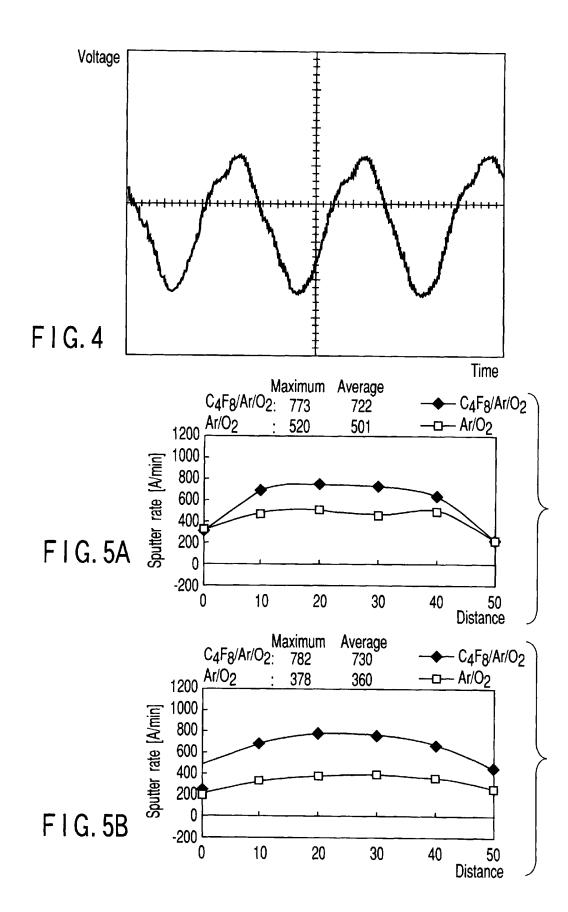
FIG.1



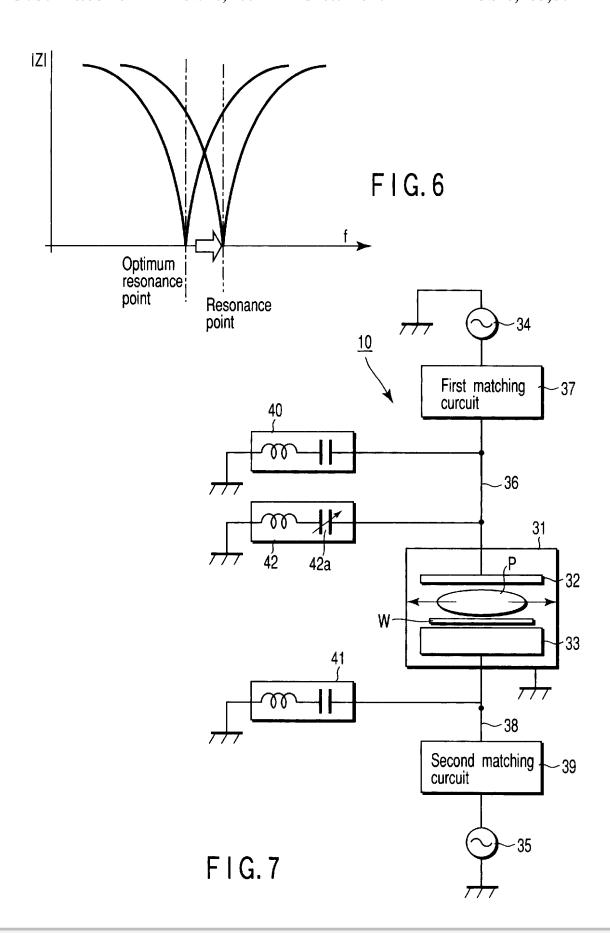
Nov. 26, 2002













DOCKET A L A R M

Explore Litigation Insights



Docket Alarm provides insights to develop a more informed litigation strategy and the peace of mind of knowing you're on top of things.

Real-Time Litigation Alerts



Keep your litigation team up-to-date with **real-time** alerts and advanced team management tools built for the enterprise, all while greatly reducing PACER spend.

Our comprehensive service means we can handle Federal, State, and Administrative courts across the country.

Advanced Docket Research



With over 230 million records, Docket Alarm's cloud-native docket research platform finds what other services can't. Coverage includes Federal, State, plus PTAB, TTAB, ITC and NLRB decisions, all in one place.

Identify arguments that have been successful in the past with full text, pinpoint searching. Link to case law cited within any court document via Fastcase.

Analytics At Your Fingertips



Learn what happened the last time a particular judge, opposing counsel or company faced cases similar to yours.

Advanced out-of-the-box PTAB and TTAB analytics are always at your fingertips.

API

Docket Alarm offers a powerful API (application programming interface) to developers that want to integrate case filings into their apps.

LAW FIRMS

Build custom dashboards for your attorneys and clients with live data direct from the court.

Automate many repetitive legal tasks like conflict checks, document management, and marketing.

FINANCIAL INSTITUTIONS

Litigation and bankruptcy checks for companies and debtors.

E-DISCOVERY AND LEGAL VENDORS

Sync your system to PACER to automate legal marketing.

